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(54) Title: UNDERLAYER COMPOSITION FOR PROMOTING SELF ASSEMBLY AND METHOD OF MAKING AND USING

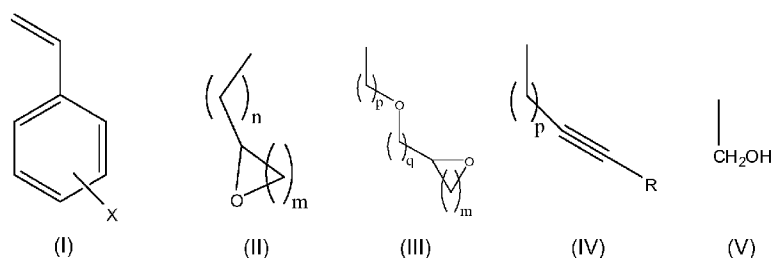
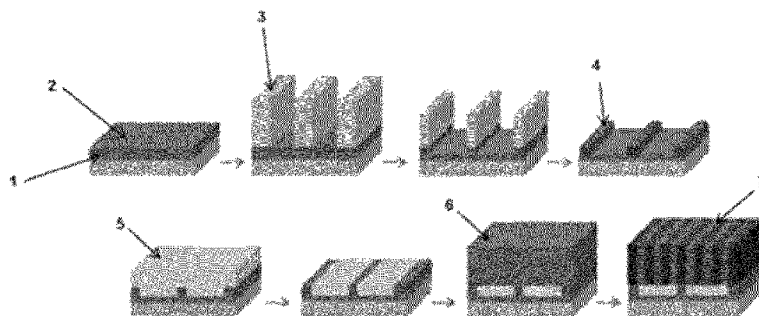


Figure 2

(57) Abstract: Disclosed herein is an underlayer composition, wherein the underlayer is typically used for promoting the formation of self assembled structures, and wherein the underlayer formulation comprises: (a) a polymer comprising at least one monomer repeat unit having the structure (I) wherein X is a crosslinking group chosen from formulae (II), (III), (IV), (V) and wherein n is 0-5, p is 0-5, q is 1-2, m is 1-2 and R is H, C₁-C₄alkyl or tri (C₁-C₄alkyl)silyl; (b) at least one thermal acid generator; and (c) a solvent. The invention further relates to methods of making and using the composition.